

What is claimed is:

1. An apparatus used in production of semiconductor ingots using the Czochralski

method comprising:

a crucible suitable for containing a melt;

a bowl-shaped susceptor at least partially disposed around and supporting the crucible, wherein the susceptor has a plurality of ventilation holes allowing any gas introduced between the crucible and the susceptor to escape through the ventilation holes.

2. The apparatus according to claim 1 wherein the susceptor is a graphite susceptor.

3. The apparatus according to claim 1, wherein the susceptor contains a protective coating.

4. The apparatus according to claim 3, wherein the protective coating is a silicon carbide coating.

5. The apparatus according to claim 1, wherein at least a portion of the ventilation holes are spaced vertically along at least a portion of the susceptor.